



DOCKET NO.: 4616/CON

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

IN THE MATTER OF THE APPLICATION FOR PATENT

OF: Hirokazu KUGAI et al.

SERIAL NO.: 10/725,860

FILED: December 1, 2003

FOR: Method of producing Negative  
Electrode for Lithium Secondary  
Cell

COMMISSIONER FOR PATENTS  
P.O. BOX 1450  
ALEXANDRIA, VA 22313-1450

February 25, 2004

INFORMATION DISCLOSURE STATEMENT AND CERTIFICATE OF MAILING

Dear Sir:

- 1) Pursuant to 37 C.F.R. §§ 1.56, 1.97 and 1.98 applicants enclose a First Form PTO-1449 and copies of references AF to AH, AM to AP and AS as listed thereon. Copies of references AA to AE, AI to AL, AQ and AR are available in the official file of the parent application USSN: 09/884,633 of this Continuation application, and need not be filed again herein. Applicants request that the references be made of record herein.
  
- 2) This Information Disclosure Statement is being filed within three months of the filing date of the above identified patent application. Thus, no fee is due for this IDS.

- 3) References AA to AE, AI, and AQ to AS are in English. References AF to AH, and AJ to AP are each accompanied by an English Abstract. Reference AK corresponds to AI, and AP corresponds to AS, from which the relevance can respectively be determined in English. References AJ and AK are discussed at page 1 of the present specification. Therefore, no further discussion of the references is required.
- 4) For further information, we are enclosing a copy of a translation of a Japanese Office Action issued on November 25, 2003 in Japanese Application 2000-382174, which is the foreign priority application of U. S. Application 09/884,632 which is related to U. S. Application 09/884,633, which is the parent of the present Continuation. Thus, the Japanese Office Action is not directly relevant to the present application, but may be pertinent to certain related or overlapping subject matter. The Japanese Examiner's remarks are not ratified as being accurate, but are merely submitted for the U. S. Examiner's consideration.
- 5) Applicants respectfully request that the Examiner consider all references of record, return an initialled copy of the enclosed second Form PTO-1449 and ensure that all references of record are printed on any patent issuing from this application.



Favorable consideration and allowance of claims 1 to 48 are respectfully requested.

Respectfully submitted,

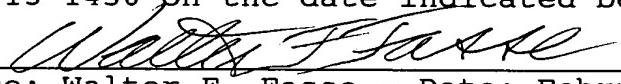
Hirokazu KUGAI et al.  
Applicant

WFF:ar/4616/CON  
Enclosure: postcard,  
1 Form PTO-1449,  
Translation of Japanese Office  
Action, 8 references,  
7 Eng. Abstracts

By   
Walter F. Fasse  
Patent Attorney  
Reg. No.: 36132  
Tel. No.: 207-862-4671  
Fax. No.: 207-862-4681  
P. O. Box 726  
Hampden, ME 04444-0726

CERTIFICATE OF MAILING:

I hereby certify that this correspondence with all indicated enclosures is being deposited with the U. S. Postal Service with sufficient postage as first-class mail, in an envelope addressed to: COMMISSIONER FOR PATENTS, P.O. BOX 1450, ALEXANDRIA, VA 22313-1450 on the date indicated below.

 2/25/04  
Name: Walter F. Fasse - Date: February 25, 2004

**LIST OF REFERENCES CITED BY  
APPLICANT  
(REVISED FORM PTO-1449)**

**DATED: February 25, 2004**

O I P E  
U. S. PATENT DOCUMENTS  
MAR 01 2004  
RECEIVED  
U. S. PATENT AND TRADEMARK OFFICE  
SEARCHED INDEXED  
SERIALIZED FILED

Applicant: Hirokazu KUGAI et al.

U.S. Filing Date:  
December 1, 2003

Art Unit:

**U. S. PATENT DOCUMENTS**

*EXAMINER INITIAL		DOCUMENT NO.							DATE	NAME		Cl.	Sub-Cl.	Fil. Date
	AA	5	1	4	1	6	1	4	08/1992	Akridge et al.		-	-	-
	AB	5	3	3	8	6	2	5	08/1994	Bates et al.		-	-	-
	AC	5	5	6	1	0	0	4	10/1996	Bates et al.		-	-	-
	AD	5	9	6	1	6	7	2	10/1999	Skotheim et al.		-	-	-
	AE	6	1	6	8	8	8	4	01/2001	Neudecker et al.		-	-	-

**FOREIGN PATENT DOCUMENTS**

		DOCUMENT NO.							DATE	COUNTRY	Cl.	Sub-Cl.	Trans.	
													Yes	No
*	AF	56	1	5	6	6	7	4	12/1981	Japan	-	-	Abst.	
,	AG	60	0	7	2	1	7	0	04/1985	Japan	-	-	Abst.	
,	AH	08	1	6	7	4	2	5	06/1996	Japan	-	-	Abst.	
Y	AI	0	2	0	6	3	3	9	12/1986	Europe	-	-	x	
X	AJ	62	0	4	4	9	6	0	02/1987	Japan	-	-	Abst.	
X	AK	05	0	4	8	5	8	2	07/1993	Japan	-	-	Abst. +=AI	
X	AL	10	0	5	8	0	0	7	03/1998	Japan	-	-	Abst.	
.	AM	10	0	8	3	8	3	8	03/1998	Japan	-	-	Abst.	
.	AN	W000	/	2	8	6	0	8	05/2000	PCT	-	-	Abst.	
.	AO	2001	2	8	4	0	4	8	10/2001	Japan	-	-	Abst.	
>	AP	2002	0	1	5	7	2	8	01/2002	Japan	-	-	Abst. +=AS	

**OTHER DOCUMENTS**

AQ	Description of MRC sputtering system given at <a href="http://www.sctsystems.com/mrc/903/system.html">http://www.sctsystems.com/mrc/903/system.html</a>
AR	US Patent Application Publication No. US 2002/0028383 A1, published on March 7, 2002, Kugai et al., Title: Thin Alkali Metal Film Member and Method of Producing the Same; Cover page, 1 sheet of drawings, and pages 1 to 6
AS	US Patent Application Publication No. US 2003/0180608A1, published on September 25, 2003, Mori et al., Title: Lithium Secondary Cell and Method for Manufacture Thereof; cover page, 2 sheets of drawings, and pages 1 to 3.

EXAMINER

DATE

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.